00862.022246

## PATENT APPLICATION

APR 3 0 2003

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)	
W	:	Examiner: H. Nguyen
Kazunori IWAMOTO et al.	)	Group Art Unit: 2851
Application No.: 09/866,600	)	Group Art Omt. 2001
Filed: May 30, 2001	:	
For: STAGE APPARATUS WHICH SUPPORTS	:	April 30, 2003
INTERFEROMETER, STAGE POSITION	:	
MEASUREMENT METHOD, PROJECTION	)	
EXPOSURE APPARATUS, PROJECTION	:	
EXPOSURE APPARATUS MAINTENANCE	)	
METHOD, SEMICONDUCTOR DEVICE	:	
MANUFACTURING METHOD, AND	)	
SEMICONDUCTOR MANUFACTURING FACTORY	<i>'</i> :	
The Commissioner for Patents		
Washington, D.C. 20231		

## **AMENDMENT**

Sir:

In response to the Official Action dated January 30, 2003, please amend the aboveidentified application as follows:

## **INTRODUCTORY COMMENTS**

This Amendment has been prepared in accordance with the Revised Format established by the U.S. Patent and Trademark Office, as permitted in the Pre-OG Notice dated February 4, 2003, and entitled "Amendments in a Revised Format Now Permitted."